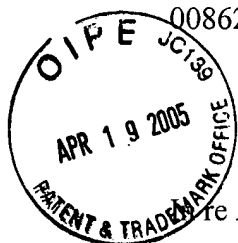


IFW



00862.023131.

PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Re Application of:)	
	:	Examiner: J.D. Lee
HARUHITO ONO ET AL.	:	
	:	Group Art Unit: 2874
Application No.: 10/615,955)	
	:	
Filed: July 10, 2003)	
	:	
For: MULTI-CHARGED BEAM LENS,)	
CHARGED-PARTICLE BEAM	:	
EXPOSURE APPARATUS)	
USING THE SAME, AND	:	
DEVICE MANUFACTURING)	
METHOD	:	April 18, 2005

MAIL STOP
Commissioner for Patents
PO Box 1450
Alexandria, VA 22313-1450

RESPONSE TO RESTRICTION REQUIREMENT

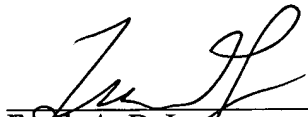
Sir:

In response to the Office Action dated March 25, 2005, Applicants elect, without traverse, to proceed initially with examination of Group I (Claims 1-19).

Applicants respectfully request favorable consideration on the merits and early passage to issue of the elected claims.

Applicants' undersigned attorney may be reached in our New York office by telephone at (212) 218-2100. All correspondence should continue to be directed to our below listed address.

Respectfully submitted,



Frank A. DeLucia
Attorney for Applicants
Registration No. 42,476

FITZPATRICK, CELLA, HARPER & SCINTO
30 Rockefeller Plaza
New York, New York 10112-3801
Facsimile: (212) 218-2200

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